

A Millimeter-Wave Wideband SPDT Switch with Traveling-Wave Concept Using 0.13- μm CMOS Process

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Abstract — A wideband SPDT switch in standard bulk 0.13- μm CMOS process is demonstrated in this paper. In order to extend the operation frequency, the traveling-wave circuit topology is utilized. Due to the different requirements in the transmit and receive paths, the switch is designed to be asymmetric. In the receive path, the switch achieves a measured insertion loss less than 2.7 dB, a measured isolation better than 26 dB from 27 to 50 GHz. On the other hand, for the transmit path, the switch also achieves a measured insertion loss less than 4.4 dB, and an isolation better than 14 dB from 30 to 63 GHz. At 40 GHz, a measured input P_{1dB} of 13.8 dBm is attained. The chip size is only 0.8 x 0.5 mm². The measured data agree with the simulation results well. To our knowledge, this work is the first CMOS switch in millimeter-wave frequency range.

Index Terms — CMOS, SPDT switch, traveling wave.

I. INTRODUCTION

In recent years, wireless communication systems have undergone explosive growth that is largely unanticipated. In time-division duplexing (TDD) communication systems, T/R switch plays an important role to change the RF signal flow to transmitter or receiver. To further increase the integration level, the SPDT switch has to be integrated in the transceiver. CMOS technology has been able to meet the more stringent cost constraints inherent in these more diverse mainstream applications. The advantages of silicon CMOS technology for RF and microwave control functions over GaAs are its low cost, compatibility with 3.3-V portable systems, and the integration potential with RF and silicon MOS-based mixed-signal circuitry.

Switches using CMOS processes were reported [1]-[4]. However, due to the limit of the CMOS process and circuit topology, the frequency range of CMOS RF switches is mostly lower than 5.8 GHz. The conventional topology for CMOS switch is series-shunt, which can not meet the wideband frequency requirement. A different topology of narrow-band CMOS switch is reported [5]. It demonstrates the power performance of a CMOS switch, but the LC-tuned substrate bias network limits the frequency response. For broadband frequency response, a number of switches using HEMT or MESFET process based on traveling-wave concept are reported [6]-[9]. These switches combined the off-state shunt transistors and series microstrip lines to form an

artificial transmission line with 50- Ω characteristic impedance and achieve wide bandwidth.

In this paper, a CMOS RF SPDT switches in standard bulk 0.13- μm CMOS process is presented. By using the traveling-wave concept, this chip demonstrated wideband frequency response. The CMOS SPDT switch exhibits 2.7-dB measured insertion loss, 26-dB isolation from 27 to 50 GHz in the receive path, and 4.4-dB insertion loss, 14-dB isolation from 30 to 63 GHz in the transmit path. It also accomplishes 13.8-dBm P_{1dB} in the transmit path at 40 GHz with a miniature chip size of 0.4 mm². To our knowledge, this work demonstrates the first CMOS switch in millimeter-wave frequency range.

II. DEVICE CHARACTERISTICS AND MMIC PROCESS

The SPDT switch is fabricated in a 0.13- μm bulk CMOS process. This process provides single poly layer for the gates of the MOS and eight metal layers for inter-connection. Using optimized CMOS topology and deep n-well (DNW), this topology provides a f_T of 85 GHz and f_{MAX} of 90 GHz at maximum-transconductance bias. A MIM capacitor of 1ff/ μm^2 has been developed using oxide inter-metal dielectric. Two types of polysilicon resistors, with several Ω/\square and $\text{k}\Omega/\square$, are provided by choosing the individual dose of ion-implantation separately from the gate electrode doping process. DNW is offered as default in 0.13- μm mixed-signal process for better substrate noise isolation because of an additional PN junction.

III. CIRCUIT DESIGN

In the conventional GaAs-based HEMT switch designs using traveling-wave concept, large chip areas for ground-via holes are needed, which bring the parasitic inductances and will affect the performance in the high frequencies. Fig. 1(a) shows the schematic of a conventional shunt switch using common-source HEMTs. It is noted that an additional transmission line between the signal path and the shunt FET is required. This is to eliminate undesirable coupling effect between the signal line and ground via-holes [9]. In this 0.13- μm CMOS process, the ground via-hole can be omitted and the device layout is more compact, as shown in Fig. 1(b). The

line between the signal path and the device is very short so that the parasitic inductance can be neglected.

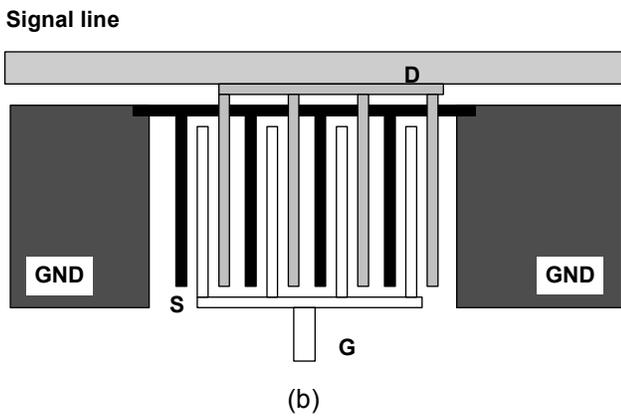
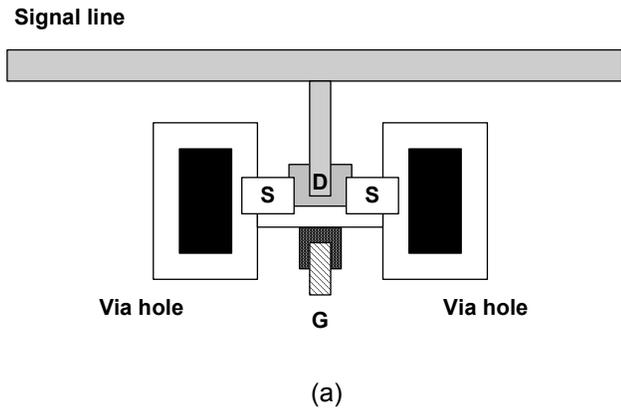


Fig. 1. Schematics of a conventional shunt switch using common-source (a) HEMTs, and (b) CMOS.

In order to reduce the loss of the transmission line in CMOS process, the thin film microstrip line is adopted [10]. Since there are eight metal layers available in this 0.13- μm CMOS process, metal 1 is used for the ground and the top metal for the signal line, as shown in Fig. 2. Figure 3 demonstrates the simulated insertion loss of the thin film microstrip line with line width of 10 μm and length of 300 μm . The characteristic impedance of the line is 50 Ω and the insertion loss is about 0.1 dB from dc to 100 GHz.

Figure 4 is the complete schematic of the SPDT traveling-wave switch. Two SPST switches and quarter wave-length transformers are included. Due to the different requirements in the transmit and receive paths, the switch design is designed to be asymmetric. Because of the parasitic resistance and capacitance of the transistors in on/off states, there are trade-offs between the insertion loss and isolation. In the receive path, the insertion loss is more important so the small devices are selected. On the other hand, the large devices are used in the transmit path for high power handling capability. In this design, the transistor size is 12 μm for the receive path, and 36

μm for transmit path. The BSIM3 model for the circuit simulation is provided by the foundry.

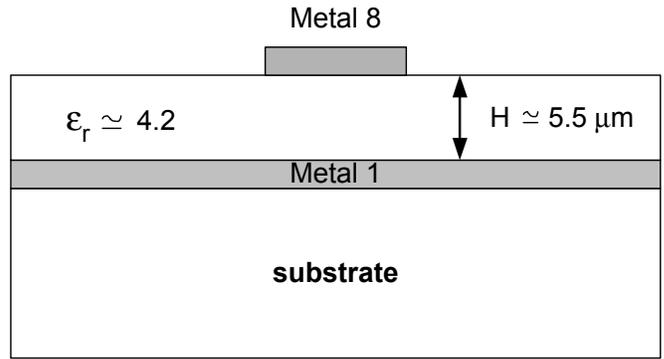


Fig. 2. The structure diagram of thin film line in 0.13 μm CMOS process.

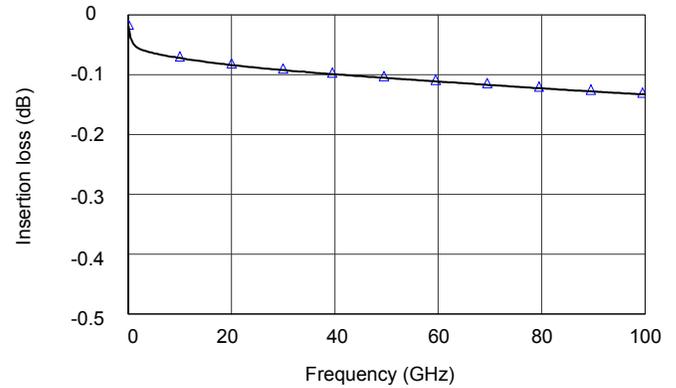


Fig. 3. Simulated insertion loss of the thin film line with line width of 10 μm and length of 300 μm .

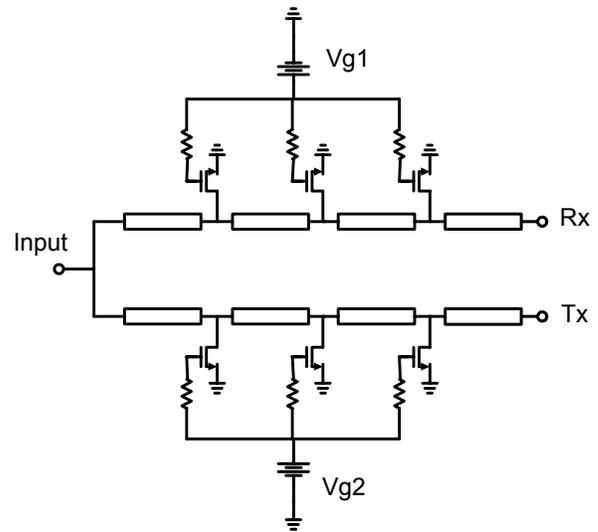


Fig. 4. Traveling-wave switch schematic.

TABLE I
SUMMARY OF MEASURED SWITCH PERFORMANCE IN TRANSMIT AND RECEIVE PATHS.

	Rx path	Tx path
Frequency (GHz)	27-50	30-63
Insertion loss (dB)	2.7	4.4
Isolation (dB)	26	14

IV. MEASUREMENT RESULTS

The die photograph of this CMOS traveling-wave SPDT switch using 0.13- μm CMOS process is shown in Fig. 5. The chip size is only $0.8 \times 0.5 \text{ mm}^2$, which is the smallest switch designed using traveling-wave concept.

The circuit was tested via on-wafer probing. Figure 6 illustrates the measured and simulated insertion loss and isolation of the switch in the receive path. The SPDT switch achieves an insertion loss of 2.7 dB and an isolation of 26 dB from 27 to 50 GHz in the receive path. Figure 7 presents the measured and simulated insertion loss and isolation of the switch in the transmit path. It also achieves an insertion loss of 4.4 dB and an isolation of 14 dB from 30 to 63 GHz in the transmit path. The measurements agree with the simulation results well. Figure 8(a) shows P_{out} v.s. P_{in} of the switch in the receive path measured from Rx port to antenna port. When the dc bias of the Tx and Rx nodes is 0 V, and V_{g1} and V_{g2} is 0 and 1.2 V respectively, the switch achieves a $P_{1\text{dB}}$ of 11.5 dBm at 40 GHz. In the transmit path, when the dc bias of the Tx and Rx nodes is 0 V, and V_{g1} and V_{g2} is 1.2 and 0 V respectively, the switch achieves a $P_{1\text{dB}}$ of 13.8 dBm at 40 GHz measured from Tx port to antenna port as shown in Fig. 8 (b). Table I summarizes the measured switch performances in transmit and receive paths.

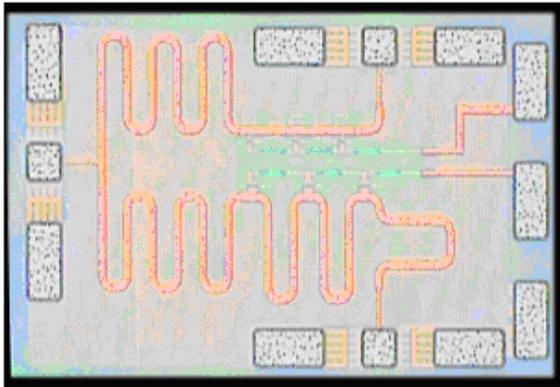


Fig. 5. Die photo of the SPDT CMOS switch. The chip size is only 0.4 mm^2 .

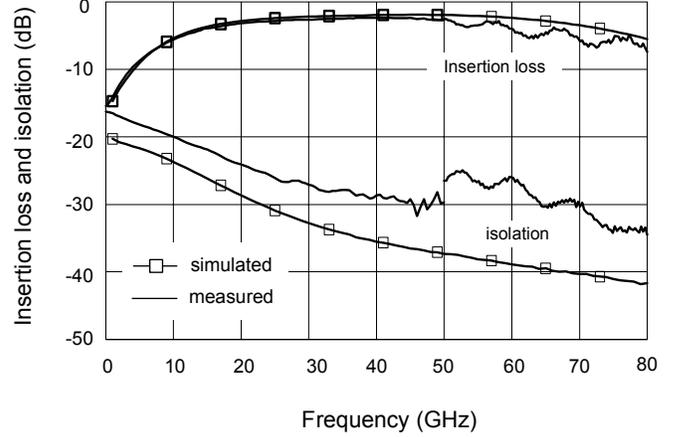


Fig. 6. Measured and simulated insertion loss and isolation of the switch in the receive path.

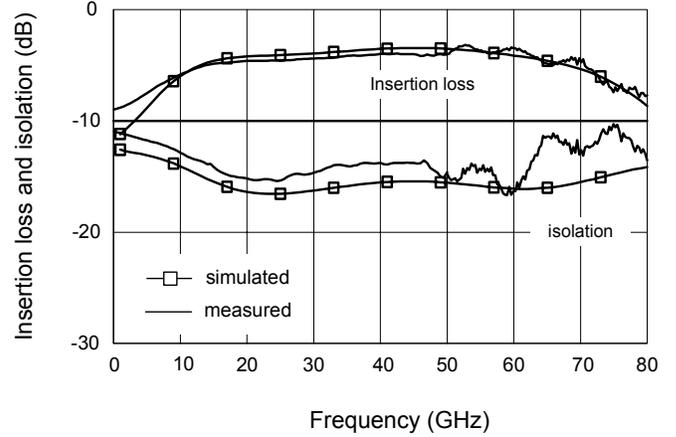


Fig. 7. Measured and simulated insertion loss and isolation of the switch in the transmit path.

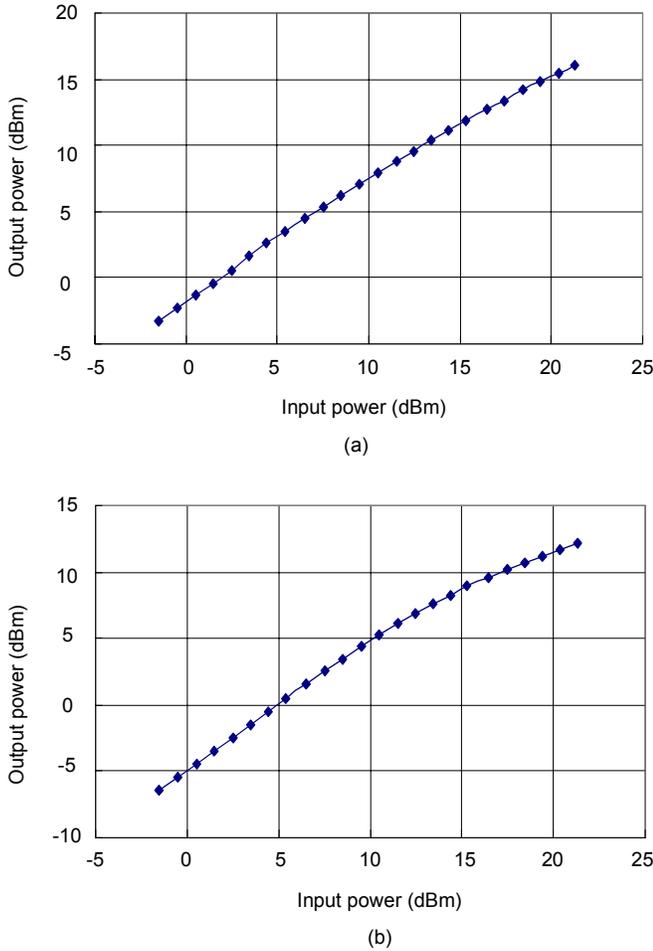


Fig. 8. Measured P_{out} v.s. P_{in} of the switch in the (a) receive path, and (b) transmit path. The input P_{1dB} is 11.5 and 13.8 dBm in the receive and transmit paths, respectively.

V. CONCLUSION

Using 0.13- μm CMOS technology, a SPDT switch has been designed, fabricated, and tested. Using traveling-wave technique, it accomplishes the wide frequency range with smallest chip size. This MMIC switch operates from 27 to 50 GHz in the receive path, and from 30 to 63 GHz in the transmit path. At 40 GHz, a measured P_{1dB} of 13.8 dBm in the transmit path is attained. The operation frequency range of the switch is the widest in CMOS process. Since the switch was fabricated using standard bulk 0.13- μm CMOS technology, it can be easily integrated with other front-end circuits to built CMOS transceivers without requiring any additional mask or post-processing steps.

ACKNOWLEDGEMENT

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